

**IN THE CLAIMS:**

**Please amend the Claims so as to read as follows:**

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1. (Amended) An active matrix substrate having electrode wiring lines arranged in a matrix form, a plurality of active elements provided at intersections of the electrode wiring lines and a plurality of pixel electrodes connected to the electrode wiring lines via the active elements on an insulating substrate, wherein

the pixel electrodes are formed of a transparent conductive oxide film made of sol-gel material [in a process preceding processes forming any constituent members of the electric wiring lines and the active elements.]

2. (Amended) An active matrix substrate as claimed in claim 1, wherein  
no constituent member of the electrode wiring lines and the active elements exists between the pixel elements and the ~~active matrix~~ insulating substrate.

3. (Cancelled)

4. (Amended) The active matrix substrate as claimed in claim 1, wherein  
the sol-gel material forming the pixel electrodes, the electrode  
wiring lines and active elements each are treated with heat, the heat treatment of  
said pixel electrodes being at a temperature higher  
than ~~those of~~ the heat treatment temperatures of the electrode  
wiring lines and the active elements.

5. (As originally filed) An active matrix substrate as claimed in claim 1,  
wherein  
the pixel electrodes are principally made of any one of indium tin  
oxide, tin oxide, indium oxide zinc oxide, germanium oxide and titanium oxide or a  
mixture of these substances.

6. (Amended) An active matrix substrate fabricating method for  
fabricating <sup>the</sup> an active matrix substrate having electrode wiring lines arranged in a  
matrix form, a plurality of active elements provided at intersections of the  
electrode wiring lines and a plurality of pixel electrodes connected to the  
electrode wiring lines via the active elements on an insulating substrate,  
comprising the step of:  
forming the pixel electrodes of a sol-gel material in a process preceding  
processes of forming constituent elements of the electrode wiring lines  
and the active elements.

7. (Amended) An active matrix substrate fabricating method according to claim 6, ~~for fabricating an active matrix substrate having electrode wiring lines arranged in a matrix form, a plurality of active elements provided at intersections of the electrode wiring lines and a plurality of pixel electrodes connected to the electrode wiring lines via the active elements on an insulating substrate, comprising the step of wherein:~~  
forming the pixel electrodes are formed by patterning a sol-gel material having photosensitivity.
8. (As originally filed) An active matrix substrate fabricating method as claimed in claim 7, wherein  
a chelating agent for imparting photosensitivity is added to the sol-gel material.
9. (As originally filed) An active matrix substrate fabricating method as claimed in claim 7, wherein  
a photosensitive resin for imparting photosensitivity is added to the sol-gel material.
10. (As originally filed) A liquid crystal display device including the active matrix substrate claimed in claim 1.
11. (As originally filed) A liquid crystal display device including the active matrix substrate fabricated by the active matrix substrate fabricating method claimed in claim 6.
12. (As originally filed) A liquid crystal display device including the active matrix substrate fabricated by the active matrix substrate fabricating method claimed in claim 7.
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